

2010 RTP

18th IEEE Conference on Advanced Thermal Processing of Semiconductors

CALL FOR PAPERS

The IEEE and RTP Conference Committee invites you to submit abstracts for the 18th IEEE Conference on Advanced Thermal Processing of Semiconductors - RTP2010. The conference will be held at the Hilton University of Florida Conference Center in Gainesville on September 28 through October 1, 2010. The conference provides an opportunity for members of the RTP community and academia to share their insight and learn more about Advanced Thermal Processing of Semiconductors. The conference brings together process and equipment engineers, managers, researchers and educators involved in Advanced Thermal Processing of Semiconductors.

The Conference is accompanied by a one day tutorial workshop "Advanced Modeling of Thermal and Ion-implantation Processes" which will be held on September 28, 2010.

The committee invites leaders in the semiconductor industry to submit papers based on all aspects of Thermal Processing of Semiconductors. All submissions should include title, list of authors with affiliations, and an abstract not exceeding 300 words. Abstracts should be submitted electronically as a Microsoft Word or Adobe PDF document. To submit a paper, please follow instructions at www.ieee-rt.org, folder Submit Abstract. Accepted papers will be published in the electronic conference proceeding with no page limit. Selected presentations will be considered for publication in IEEE Transaction on Semiconductor Manufacturing or IEEE Transaction on Electron Devices.

Important Dates:

Abstract Submission Deadline May 31, 2010

Notification of Acceptance June 14, 2010

Final Paper Submission Deadline: August 31, 2010

Conference Steering Committee:

B. Lojek – Atmel, E. Rosseel – IMEC, J. Gelpy – Mattson, K. Jones – University of Florida
M. Tanjyo – Nissin Ion Equipment, M. Current – Current Scientific



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